



## INFORMATION DISCLOSURE STATEMENT

Applicant : Leskela et al.  
App. No. : 09/787,062  
Filed : June 28, 2001  
For : METHOD FOR GROWING OXIDE THIN  
FILMS CONTAINING BARIUM AND  
STRONTIUM  
Examiner : Matthew A. Anderson  
Group Art Unit : 1765

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing 3 references that are also enclosed.

Please place these references in the file of the above-identified patent application in accordance with 37 C.F.R. § 1.97(i).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: April 2, 2004

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FORM PTO-449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
SEPP9.001APCAPPLICATION NO.  
09/787,062INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT  
Leskela et al.FILING DATE  
June 28, 2001GROUP  
1765

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
	1.	Vehkamäki et al., <u>Growth of SrTiO<sub>3</sub> and BaTiO<sub>3</sub> Thin Films by Atomic Layer Deposition</u> , Electrochemical and Solid-State Letters, 2 (10) pp. 504-506 (1999)
	2.	Nakano et al., <u>Digital chemical vapor deposition of SiO<sub>2</sub></u> , Appl. Phys. Lett 57 (11), September 10, 1990, pp. 1096-1098
	3.	S.M. Bedair, <u>Atomic layer epitaxy deposition processes</u> , J. Vac. Sci Technol. B 12(1), Jan/Feb 1994, pp. 179-185

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040204

EXAMINER	DATE CONSIDERED
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	